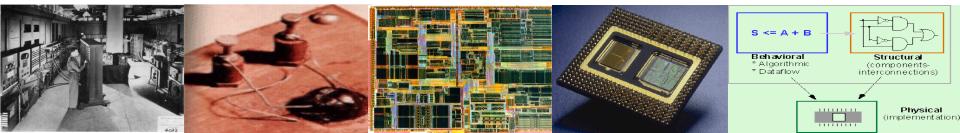
CpE 690: Introduction to VLSI Design

Lecture 8 Transient Response and Delay

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Adapted from Lecture Notes, David Mahoney Harris CMOS VLSI Design

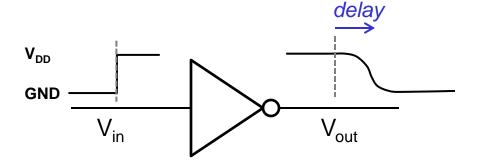


Activity

1) If the width of a transistor increases, the current will increase decrease not change If the length of a transistor increases, the current will increase decrease not change If the supply voltage of a chip increases, the maximum transistor current will decrease increase not change If the width of a transistor increases, its gate capacitance will increase decrease not change If the length of a transistor increases, its gate capacitance will increase decrease not change If the supply voltage of a chip increases, the gate capacitance of each transistor will increase decrease not change

Transient Response

- DC analysis tells us V_{out} if V_{in} is constant
- Transient analysis tells us V_{out}(t) in response to a change in V_{in}
- Requires solving differential equations
- Input is usually considered to be a step or ramp
 - From GND to V_{DD} or vice versa

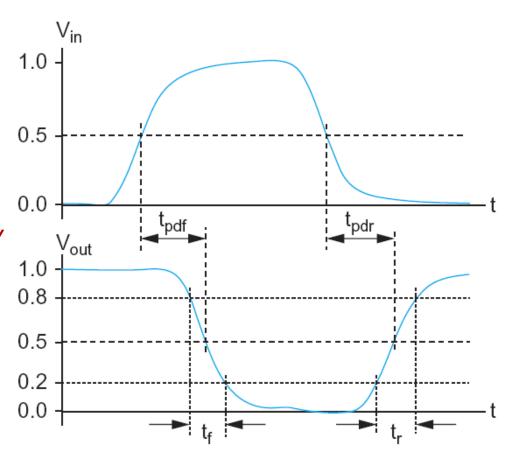


Delay Definitions

- **t**_{pdr}: rising propagation delay
 - maximum time from input crossing V_{DD}/2 to rising output crossing V_{DD}/2
- t_{pdf}: falling propagation delay
 - maximum time from input crossing V_{DD}/2 to falling output crossing V_{DD}/2
- t_{pd}: average propagation delay

$$- t_{pd} = (t_{pdr} + t_{pdf})/2$$

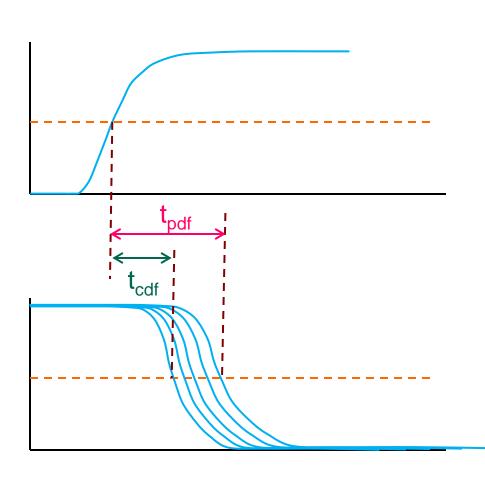
- t_r: rise time
 - from output crossing 0.2
 V_{DD} to 0.8 V_{DD}
- t_f: fall time
 - from output crossing 0.8
 V_{DD} to 0.2 V_{DD}



Delay Definitions (cont.)

- **t**_{cdf}: falling contamination delay
 - minimum time from input crossing V_{DD}/2 to falling output crossing V_{DD}/2
- **t**_{cdr}: rising contamination delay
 - minimum time from input crossing V_{DD}/2 to rising output crossing V_{DD}/2
- t_{cd}: avg. contamination delay

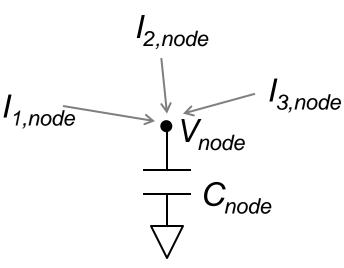
$$- t_{pd} = (t_{cdr} + t_{cdf})/2$$



Delay in CMOS Circuits

- Switching CMOS gate generates output current in response to changing input voltages
- All nodes have some finite capacitance (to ground)
 - gate capacitance
 - parasitic source/drain (diode) capacitance
 - parasitic wiring capacitance
- Transient waveforms found by solving:

$$C_{node} \cdot (dV_{node}/dt) = \sum_{k} I_{k,node}$$
 for each node in circuit



Inverter Step Response

Find step response of inverter driving C_{load}

$$V_{in}(t) = u(t - t_0) \cdot V_{DD}$$

$$V_{out}(t < t_0) = V_{DD}$$

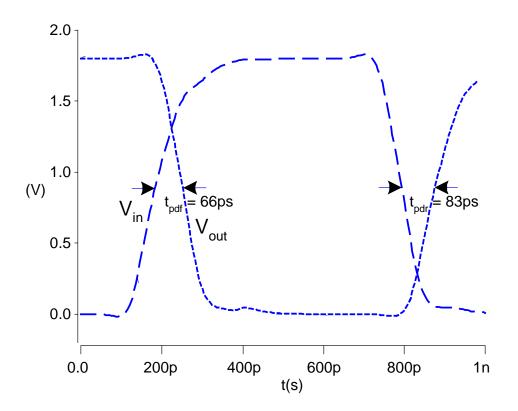
$$dV_{out}(t)/dt = -I_{dsn}(t)/C_{load}$$

$$I_{dsn}(t) = \begin{cases} 0 & \text{for } t < t_0 \\ (\beta/2) \cdot (V_{DD} - V_t)^2 & \text{for } V_{out} > V_{DD} - V_t \\ \beta \cdot (V_{DD} - V_t - V_{out}(t)/2) \cdot V_{out}(t) & \text{for } V_{out} < V_{DD} - V_t \end{cases}$$

$$7$$

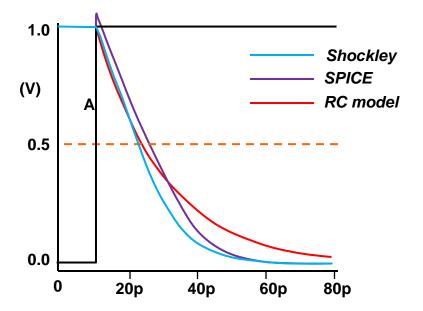
Simulated Inverter Delay

- Solving differential equations by hand is too hard
- SPICE simulator solves the equations numerically
- Uses more accurate I-V models too!
- But simulations take time to write!



Delay Estimation

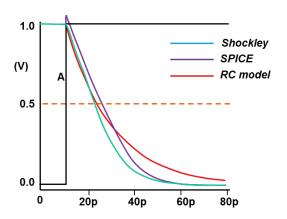
- We would like to be able to easily estimate delay
 - For exploration of design space, don't need to be as accurate as simulation
 - Want a technique where its easier to ask "What if?"
- The step response usually looks like a 1st order RC response with a decaying exponential.
- Can we model conducting transistor as effective resistance?



Effective Resistance

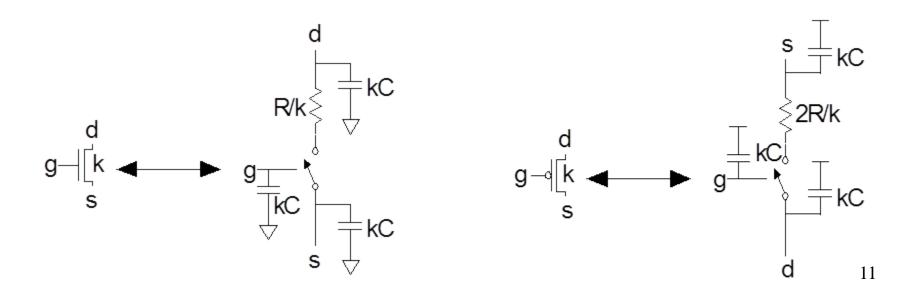
- Simplification: treat transistor as resistor
 - Replace $I_{ds}(V_{ds}, V_{gs})$ with effective resistance R
 - $-I_{ds} = V_{ds}/R$ or 0 depending on gate voltage

- R averaged across switching of digital gate
 - Too inaccurate to predict current at any given time
 - But good enough to predict gate delay



RC Delay Model

- Use equivalent circuits for MOS transistors
 - Ideal switch + capacitance and ON resistance
 - Unit nMOS has resistance R, capacitance C
 - Unit pMOS has resistance 2R, capacitance C
- Capacitance (gate & diffusion) proportional to width
- Resistance inversely proportional to width



RC Values

Capacitance

- $C = C_g = C_s = C_d = 2 \text{ fF/}\mu\text{m}$ of gate width in 0.6 μm
- Gradually decline to 1 fF/μm in nanometer techs.

Resistance

- R \approx 5-10 K Ω • μ m in 0.6 μ m process
- Improves with shorter channel lengths

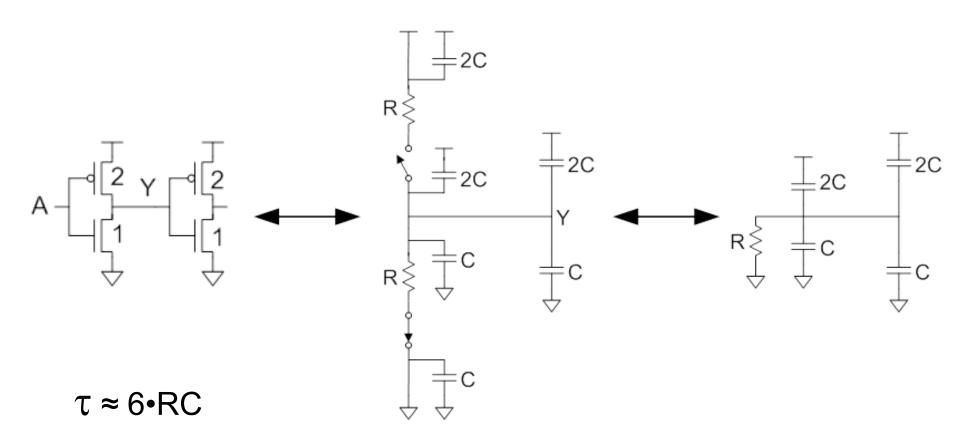
Unit transistors

- May refer to minimum contacted device (4/2 λ)
- Or maybe W=1 μm device (doesn't matter as long as you are consistent)

	AMI 0.6μm	TSMC 250nm	TSMC 180nm	IBM 130nm	IBM 65nm
R_n (k Ω . μ m)	9.2	4.0	2.7	2.5	1.3
R_n (k Ω .4 λ)	7.7	8.0	7.5	9.6	10
$R_p (k\Omega.\mu m)$	19.9	8.9	6.5	6.4	2.9
$R_{\rm p} \ (k\Omega.4\lambda)$	16.6	17.8	18.1	24.7	22.3

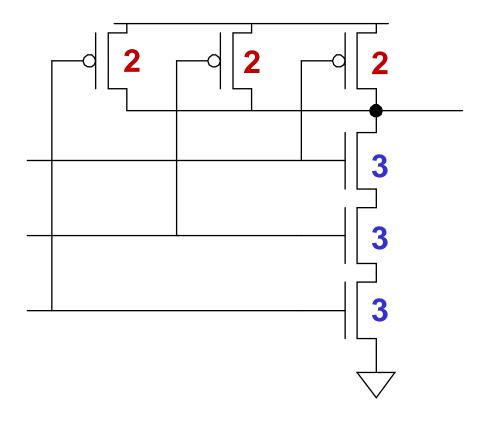
RC Values

Estimate the delay of a fanout-of-1 inverter



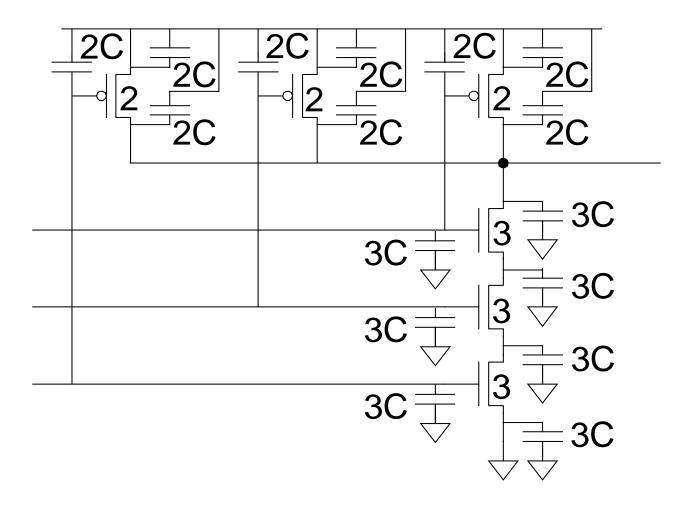
Example: 3-input NAND

 Sketch a 3-input NAND with transistor widths chosen to achieve (worst case) effective rise and fall resistances equal to a unit inverter (R).



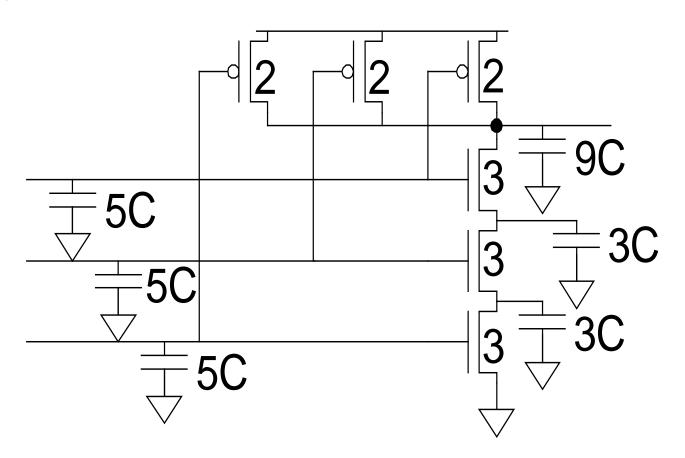
3-input NAND Capacitors

 Annotate the 3-input NAND gate with gate and diffusion capacitance.



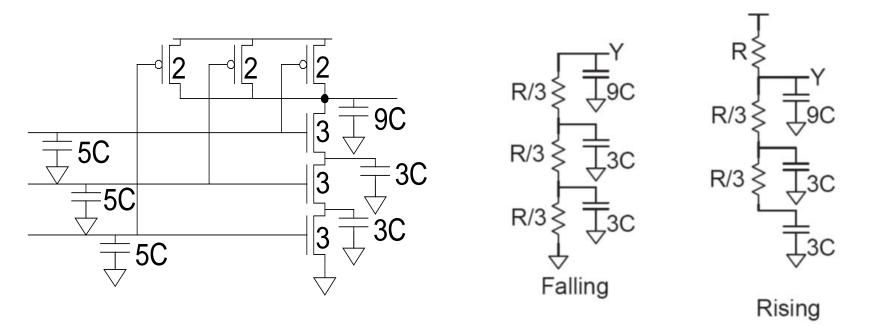
3-input NAND Capacitors

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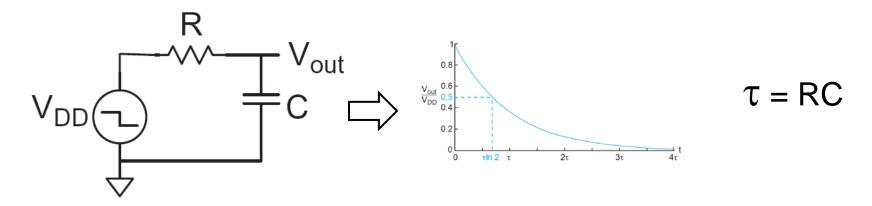
Rise & Fall Delay

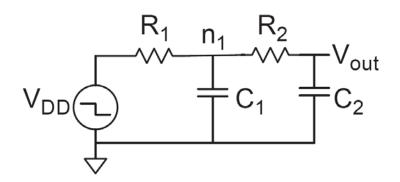
What are worst-case rise and fall delays?



How can we estimate delay of these networks?

τ with multiple RC components





$$H(s) = \frac{1}{1 + s[R_1C_1 + (R_1 + R_2).C_2] + s^2R_1C_1R_2C_2}$$

- Second order response is too complicated
 - defeats whole purpose of simplifying to an RC network
- Can approximate to:

$$\tau = \tau_1 + \tau_2 = R_1C_1 + (R_1 + R_2).C_2$$

Elmore Delay

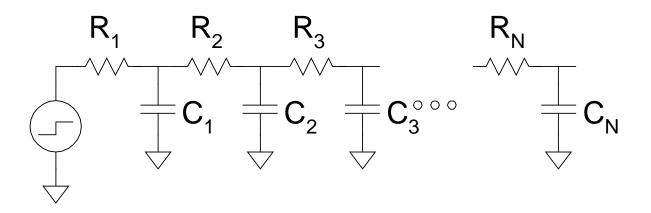
- ON transistors modeled as resistors
- Pullup or pulldown network represented as an RC tree
 - root of tree is driving voltage source (often VDD or GND)
 - leaves are capacitors at end of branches
- Elmore delay to any target (node j) in the branch:

$$t_{pdj} = \sum_{i} R_{sij}. C_i$$

where:

- i represents <u>all</u> the nodes in the branch
- C_i is the capacitance at node i
- R_{sij} is the resistance of the shared path from the source to $node_i$ and from the source to the target $node_i$
- Elmore delay is conservative
 - over-estimates the delay

Shared Path



delay to node N is:

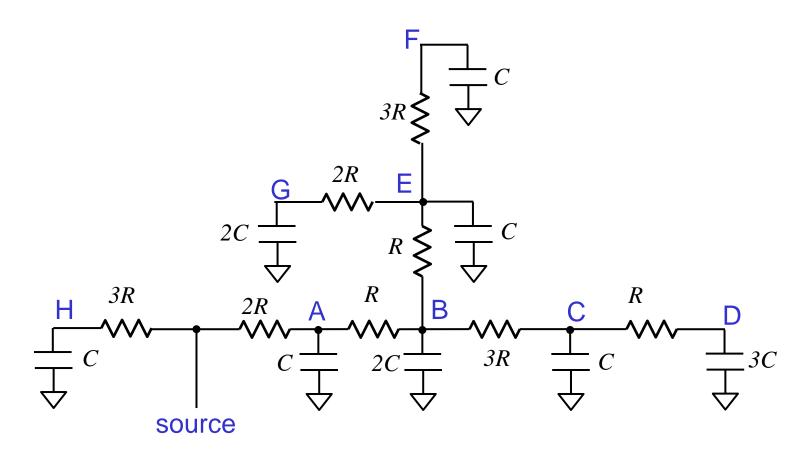
$$R_1C_1 + (R_1+R_2).C_2 + ... + (R_1+R_2+...+R_n).C_N$$

delay to node 2 is:

$$R_1C_1 + (R_1+R_2).C_2 + (R_1+R_2).(C_3+C_4+...+C_N)$$

Example: Elmore Delay

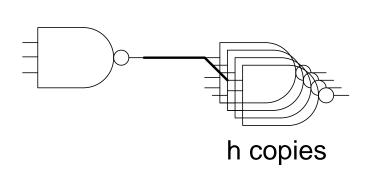
Calculate delay from source to all nodes in circuit:

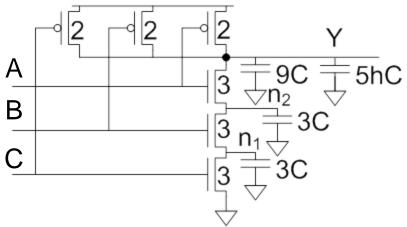


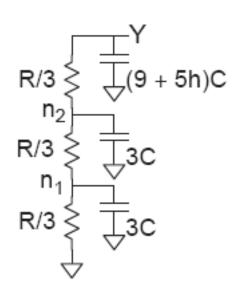
3-input NAND: pull-down delay

Estimate worst-case rising and falling delay of 3-input NAND

driving *h* identical gates.





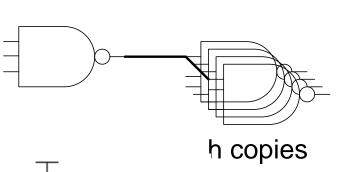


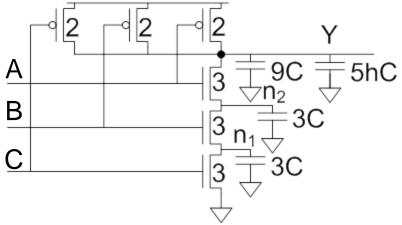
Worst case pull-down delay occurs when ABC goes from (110) to (111)

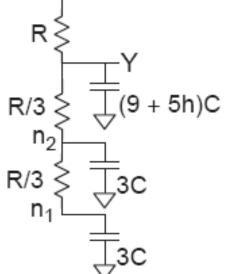
$$t_{pdf} = (3C)(\frac{R}{3}) + (3C)(\frac{R}{3} + \frac{R}{3}) + [(9+5h)C](\frac{R}{3} + \frac{R}{3} + \frac{R}{3})$$
$$t_{pdf} = (12+5h)RC$$

3-input NAND: pull-up delay

 Estimate worst-case rising and falling delay of 3-input NAND driving h identical gates.







Worst case pull-up delay occurs when ABC goes from (111) to (110)

$$t_{pdr} = [(9 + 5h)C](R) + (3C)(R) + (3C)(R)$$

$$t_{pdr} = (15 + 5h)RC$$

Delay Components

$$t_{pdf} = (12 + 5h)RC$$

$$t_{pdr} = (15 + 5h)RC$$

- Delay has two parts
 - Parasitic delay
 - 15 or 12 RC
 - Independent of load
 - Effort delay
 - 5h RC
 - Proportional to load capacitance

Contamination Delay

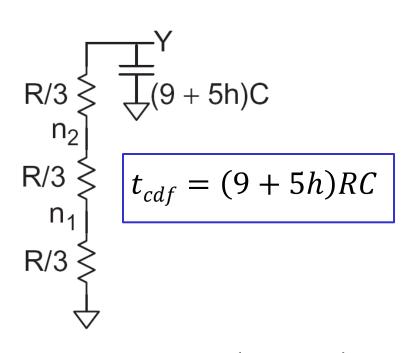
 Best-case (contamination) delay can be substantially less than propagation delay:

if top nMOS is last to turn on:

i.e. ABC goes from (011) to (111)

if all pMOS turn on simultaneously:

i.e. ABC goes from (111) to (000)



$$R \stackrel{\stackrel{}{\underset{}}}{\underset{}} R \stackrel{\stackrel{}{\underset{}}}{\underset{}} R \stackrel{\stackrel{}{\underset{}}}{\underset{}} Y$$

$$\stackrel{}{\underset{}} U$$

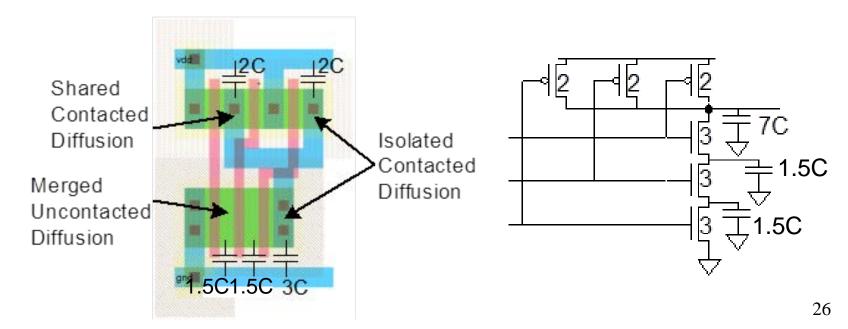
$$t_{cdr} = \left(3 + \frac{5}{3}h\right)RC$$

compare to:
$$t_{pdf} = (12 + 5h)RC$$

$$t_{pdr} = (15 + 5h)RC$$

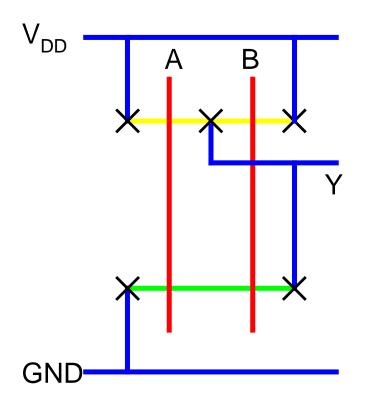
Diffusion Capacitance

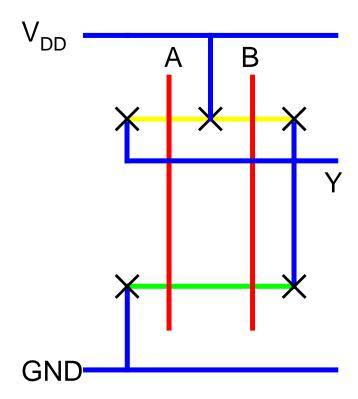
- We assumed contacted diffusion on every s / d.
 - but shared on series nMOS chain
- Good layout minimizes diffusion area
- Good NAND3 layout shares one diffusion contact
 - Reduces output capacitance by 2C
- Merged un-contacted diffusion also helps



Layout Comparison

Which layout is better?





Example: Gate delays

For the gate $Y = \overline{A + B.C}$

- a) Draw the schematic
- b) Size the transistors to give pullup and pulldown strength equal to unit size inverter
- c) Annotate with effective R of each transistor and C of each node
- d) Calculate worst case rising & falling propagation delay while driving h similar gates (via input B)
- e) Calculate best case rising & falling contamination delay while driving h similar gates (via input B)